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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of

Kyoung Hwan Chin

Group Art Unit: 1746

Serial No.: 09/988,302

Examiner: Winter, Gentle E.

Filed: 19 November 2001

For: CLEANING APPARATUS OF HIGH
DENSITY PLASMA CHEMICAL VAPOR
DEPOSITION CHAMBER AND
CLEANING METHOD THEREOF

RESPONSE TO ELECTION/RESTRICTION REQUIREMENT

U.S. Patent and Trademark Office
2011 South Clark Place
Customer Window, **Mail Stop Non-Fee Amendment**
Crystal Plaza Two, Lobby, Room 1B03
Arlington, VA 22202

Sir:

In response to the Office Action of 2 December 2003, Applicants elect the invention of Group I, Claims 1-5, drawn to an apparatus. The election is without traverse.

Respectfully submitted,

VOLENTINE FRANCOS, PLLC

Kenneth D. Springer
Registration No. 39,843

12200 Sunrise Valley Drive, Suite 150
Reston, Virginia 20191
Telephone No.: (703) 715-0870
Facsimile No.: (703) 715-0877

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